**Substrates**

|  |  |  |
| --- | --- | --- |
| **MATERIAL** | **FORMAT** | **SIZE** |
| Si (111) | wafer | 4 inch |
| Si <111> (20 nm, SiO2) | wafer | 4 inch |
| Si <111> ( 1um, SiO2) | wafer | 3 inch |
| Si <100> | wafer | 2 inch |
| Glass | slide | 3 x 2 inch |
| ITO | slide | 2 x 2 inch |

**Thin layer deposition**

|  |  |  |
| --- | --- | --- |
| **MATERIAL** | **DEPOSITION** | **THICK RANGE** |
| Al | Sputtering DC | 5-300nm |
| Au | Sputtering DC | 5-300nm |
| Au | Thermal evaporation | 5-200nm |
| Cr | Electron Beam | 5-200nm |
| SiO2 | Electron Beam | 5-200nm |
| Al2O3 | Electron beam | 5-200nm |
| Ti | Electron Beam | 5-200nm |

**Resist materials**

|  |  |  |  |  |  |  |
| --- | --- | --- | --- | --- | --- | --- |
| **RESIST** | **DEPOSITION** | **THICKNESS** | **DEVELOPER** | **REMOVER** | **TYPE** | **EXPOSURE TOOL** |
| [AZ1512](http://www.microchemicals.com/micro/az_1500_series.pdf) | spinner | 0,9-2,8 µm | [AZ 726 MIF](http://www.microchemicals.com/micro/az_mif_developer.pdf) | AZ 100 Remover | positive | Mask aligner/ DWL |
| [AZ1518](http://www.microchemicals.com/micro/az_1500_series.pdf) | spinner | 0.5-2.8 µm | [AZ 726 MIF](http://www.microchemicals.com/micro/az_mif_developer.pdf) | AZ 100 Remover | positive | Mask aligner/DWL |
| [AZ5214](http://www.microchemicals.com/micro/az_5214e.pdf) | spinner | 1-3 µm | [AZ 726 MIF](http://www.microchemicals.com/micro/az_mif_developer.pdf) | AZ 100 Remover | Positive/negative | Mask aligner |
| [SU8-2010](http://www.microchem.com/pdf/SU-82000DataSheet2000_5thru2015Ver4.pdf) | spinner | 3-15 µm | SU8 developer | Remover PG | negative | Mask aligner |
| [SU8-2050](http://www.microchem.com/pdf/SU-82000DataSheet2025thru2075Ver4.pdf) | spinner | 10-50 µm | SU8 developer | Remover PG | negative | Mask aligner |
| [SU8-2100](http://www.microchem.com/pdf/SU-82000DataSheet2100and2150Ver5.pdf) | spinner | 100-250 µm | SU8 developer | Remover PG | negative | Mask aligner |
| PMMA | spinner | 50-500 nm | MIBK:IPA | Acetone | positive | e-beam lithography |

**Surface properties enhancers**

|  |  |  |
| --- | --- | --- |
| **NAME** | **PROVIDER** | **PROPERTIES** |
| [Trichloro-perfluorosilane](http://www.sigmaaldrich.com/catalog/product/aldrich/448931?lang=es&region=ES) | Sigma-Aldrich | anti-sticking layer |

**Wet etching chemicals available**

|  |  |  |
| --- | --- | --- |
| **NAME** | **PROVIDER** | **Name** |
| [Chromium etcher](http://www.sigmaaldrich.com/catalog/product/aldrich/651826?lang=es&region=ES) | Sigma-Aldrich | Ceric ammonium nitrate-based etchant |
| Glass etcher | Sigma-Aldrich | HF |
| Silicon etcher | Sigma-Aldrich | TMAH |